



00862.0022167

PATENT APPLICATION

9/14
3/7/03
JPR

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Shinichi HARA et al.

Application No.: 09/818,625

Filed: March 28, 2001

For: EXPOSURE APPARATUS, GAS REPLACEMENT
METHOD, SEMICONDUCTOR DEVICE
MANUFACTURING METHOD, SEMICONDUCTOR
FACTORY, AND EXPOSURE APPARATUS
MAINTENANCE METHOD

Examiner: D. Ben Esplin

Group Art Unit: 2851

February 28, 2003

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TECHNOLOGY CENTER 2800

The Commissioner for Patents
Washington, D.C. 20231

AMENDMENT WITH PETITION FOR EXTENSION OF TIME

Sir:

Applicants petition the Commissioner for Patents to extend the time for response to the Office Action dated August 28, 2002, for three months from November 28, 2002, up to and including February 28, 2003. A check in the amount of \$930.00 for payment of the extension fee is enclosed. Please charge any additional fee required for the extension, or credit any overpayment, to Deposit Account 06-1205.

In response to the Official Action dated August 28, 2002, please amend the above-identified application as follows:

03/04/2003 JBALINAN 00000002 09818625

01 FC:1253 930.00 OP

04/04/2003 JBALINAN 00000003 09818625

FC:1201 252.00 OP